



R₂ is selected from C₁₋₁₀ alkyl, N-oxide, dimethylamino, acetonitrile, benzyl, phenyl, benzyl mono- or di-substituted by nitro; phenyl mono- or di-substituted by nitro. R₃ is C₁₋₁₀ alkyl and R₄, R₅, R₆, and R₇ are each independently selected from hydrogen, C₁₋₁₀ alkyl, C₁N₀ alkylene, aryl or substituted aryl, halogen, nitro, and an alcohol group. X is a charge balancing ion, and n=1-10.

[0028] Compounds of the formulae I-III are well known and may be prepared as described in *Solar Energy Materials and Solar Cells*, 57, (1999), 107-125 which is hereby incorporated by reference in its entirety. In a preferred embodiment, the adsorbed electrochromophore is bis-(2-phosphonoethyl)-4,4'-bipyridinium dichloride.

[0029] The base substrate 210 and the second substrate 250 are then assembled with an electrolyte 280 placed between the ion-permeable reflective layer 240 and the nano-structured film 270 having an adsorbed redox chromophore 275. A potential applied across the cathode electrode 290 and the anode electrode 295 reduces the adsorbed redox chromophore 275, thereby producing a color change. Reversing the polarity of the potential reverses the color change. When the redox chromophore 275 is generally black or very deep purple in a reduced state, a user perceives a generally black or very deep purple color. When the redox chromophore 275 is in an oxidized state and generally clear, a user will perceive light reflected off of the ion-permeable reflective layer 240, which is generally white. In this manner, a black and white display is realized by a user.

[0030] Electrochromic display devices such as the one described above are described in greater detail in U.S. Pat. No. 6,301,038 and U.S. Pat. No. 6,870,657, both to Fitzmaurice et al., which are herein incorporated by reference.

[0031] As mentioned above, the adaptable skin 130 may be a pixilated display driven by and active or passive matrix. In another preferred embodiment, the adaptable skin 130 is an active matrix electrochromic display. Referring to FIG. 3, an active matrix electrochromic adaptable skin 300 comprises a layer of active components 305 selectively deposited on a backplane substrate 310. The backplane substrate is preferably flexible, however, it may be molded to fit the contour of a selected portable electronic device. It should be noted that the electrochromic display 300 contains 4 pixels D, E, F, and G, purely for illustrative purposes. Preferably,

the active components 305 are n-channel metal-oxide-semiconductor field-effect (NMOS) TFTs. Alternatively, the active components may be p-channel metal-oxide-semiconductor field effect (PMOS) TFTs, complementary-symmetry metal-oxide-semiconductor field effect (CMOS) TFTs, thin film diodes (TFDs), micro-electromechanical structures (MEMS), or any other type of active device capable of being matrix addressed for switching an electrochromic pixel.

[0032] An insulating layer 315 is deposited on the active components 305. The insulating layer 315 is substantially impermeable to the electrolyte 320, thereby protecting the active components 305 from the possible corrosive effects of the electrolyte 320. Preferably, the insulating layer 315 is a spin-coated polymer, such as polyimide. The insulating layer 315 is preferably reflective. The reflective property of the insulating layer 315 may be inherent in the material that comprises the layer, or reflective particles may be interspersed in the insulating layer 315.

[0033] An operable connection 325, known in the art as a via, is provided in the insulating layer for electrically connecting the drain of the active component 305 to a conductor 330. Preferably, the operable connection 325 is created via photolithographic techniques, which are well known to those skilled in the art. Each operable connection 325, or via, extends generally upwardly through the insulating layer 315 and is in electrical contact with a respective conductor 330, which preferably covers the bottom and the sides of a plurality of wells 335 formed or etched into the insulating layer 315. The operable connection 325 (i.e. via) and conductor 330 are preferably both transparent, and are preferably FTO or ITO.

[0034] The wells 335 are preferably etched in the insulating layer 315 using photolithographic techniques. Alternatively, the wells 335 are formed by mechanically embossing a deposited planar film or by application of a film containing a preformed waffle-type structure defining the wells 335.

[0035] Partitions 340 maintain electrical isolation of each well 335, and also allow the wells 335 to act as receptacles for ink-jet deposited materials. Partitions 340 may further act as a spacer between the cathode 345 and anode 350 of the adaptable skin 300, and serve to reduce ionic crosstalk between pixels through the electrolyte 320. The partitions 340 further serve the purpose of a visual boundary between each well 335, and may be sized as desired to achieve optimal appearance of each well 335. It is noted that although the partitions are shown as greatly extended generally above the wells 335, they may alternatively be generally flush with the top of the wells 335.

[0036] A semiconducting layer 360 having an adsorbed electrochromophore is deposited on the conductor 330. Preferably, the semiconducting layer 360 is a nano-structured metallic oxide semiconducting film, as described hereinbefore.

[0037] A frontplane substrate 365, which is substantially transparent, supports a substantially transparent conductor 370. The substrate 365 may be any suitable transparent material, and again may be flexible or contoured. FTO, ITO, or any other suitable transparent conductor may be used for the transparent conductor 370.

[0038] A semiconducting layer 375 is deposited on the transparent conductor 370. Preferably, the semiconducting